

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application Serial No. 09/905,286
Filing Date July 13, 2001
Inventor Cem Basceri et al.
Assignee Micron Technology, Inc.
Group Art Unit 1762
Examiner Eric B. Fuller
Attorney's Docket No. MI22-1724
Title: Chemical Vapor Deposition Methods of Forming Barium Strontium
Titanate Comprising Dielectric Layers



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RESPONSE TO DECEMBER 19, 2001 OFFICE ACTION

To: Box Non-Fee Amendment
Assistant Commissioner for Patents
Washington, D.C. 20231 **VIA U. S. EXPRESS MAIL**

From: Mark S. Matkin (Tel. 509-624-4276; Fax 509-838-3424)
Wells, St. John, Roberts, Gregory & Matkin P.S.
601 West First Avenue, Suite 1300
Spokane, WA 99201-3828

Responsive to the Office Action dated December 19, 2001, Applicant amends and remarks as follows:

AMENDMENTS

In the Specification

Please replace the paragraph beginning at line 8 on page 9 with the following clean replacement paragraph in accordance with 37 CFR § 1.121(b)(1)(ii). A marked-up version showing amendments to the specification paragraph being changed is provided in one or more accompanying pages separate from this amendment in accordance with 37 CFR § 1.121(b)(1)(iii).



Additional and/or alternate preferred processing can occur in accordance with any of our co-pending U.S. Patent Application Serial No. 09/476,516, filed on January 3, 2000, entitled "Chemical Vapor Deposition Methods Of Forming A High K Dielectric Layer And Methods Of Forming A Capacitor", listing Cem Basceri as inventor; U.S. Patent Application Serial No. 09/580,733, filed on May 26, 2000, entitled "Chemical Vapor Deposition Methods And Physical Vapor Deposition Methods", listing Cem Basceri as inventor; and U.S. Patent Application Serial No. 09/905,320, filed concurrently herewith, entitled "Chemical Vapor Deposition Methods Of Forming Barium Strontium Titanate Comprising Dielectric Layers, Including Such Layers Having A Varied Concentration Of Barium And Strontium Within The Layer", listing Cem Basceri and Nancy Alzola as inventors. Each of these is hereby fully incorporated by reference.

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